

High precision quantum device modeling using the atomistic tight-binding technique

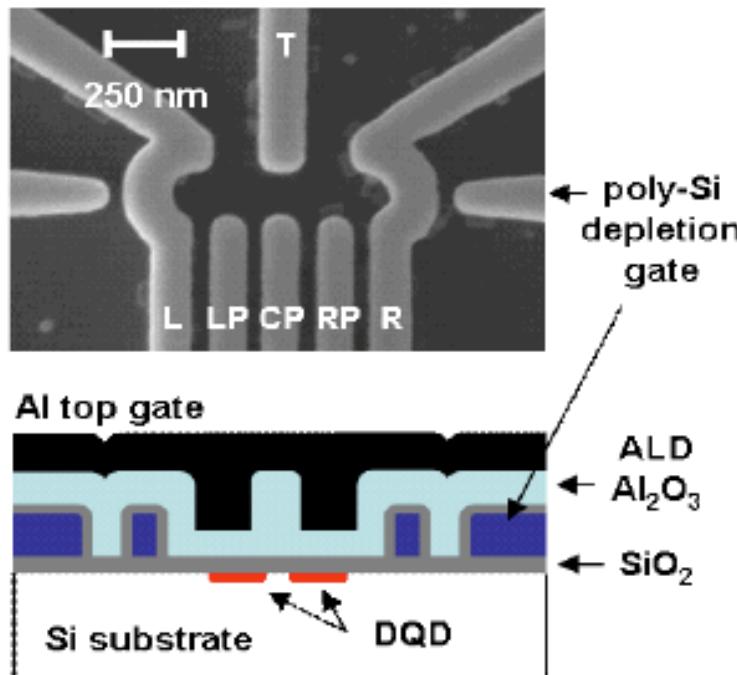
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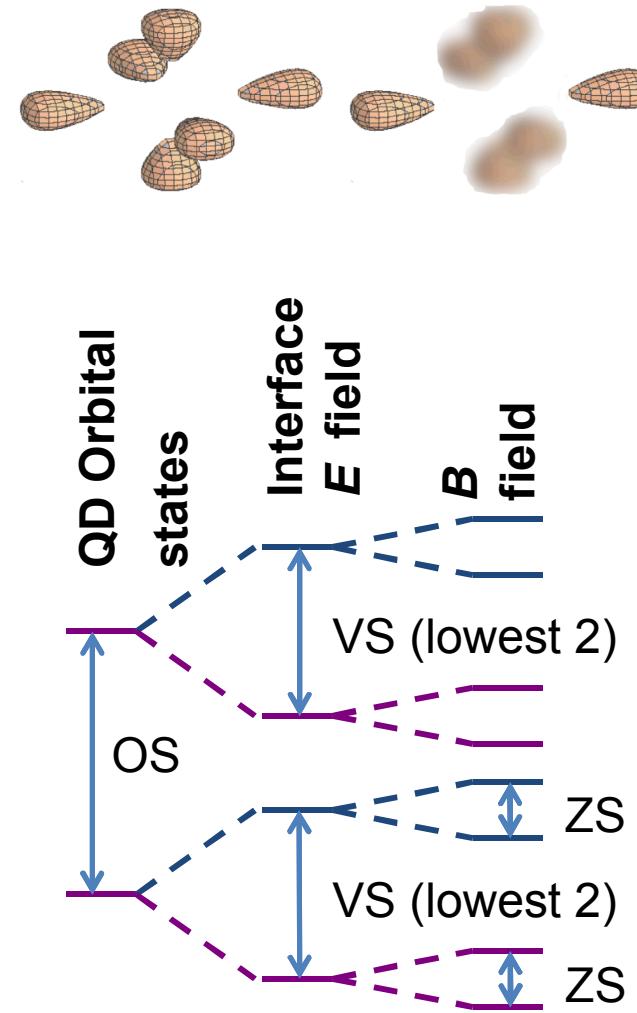
Si Quantum electronics

SNL QIST: DQD S-T Qubits in Si



Tracy et. al., APL 97, 192110 (2010)

CB valleys in Si: 2-4 splitting



Method: TB+FCI

Good 1e wfs

+

Full CI for few electrons

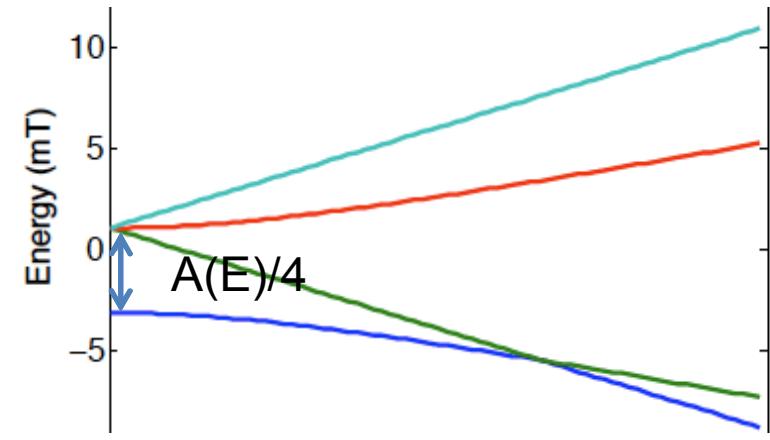
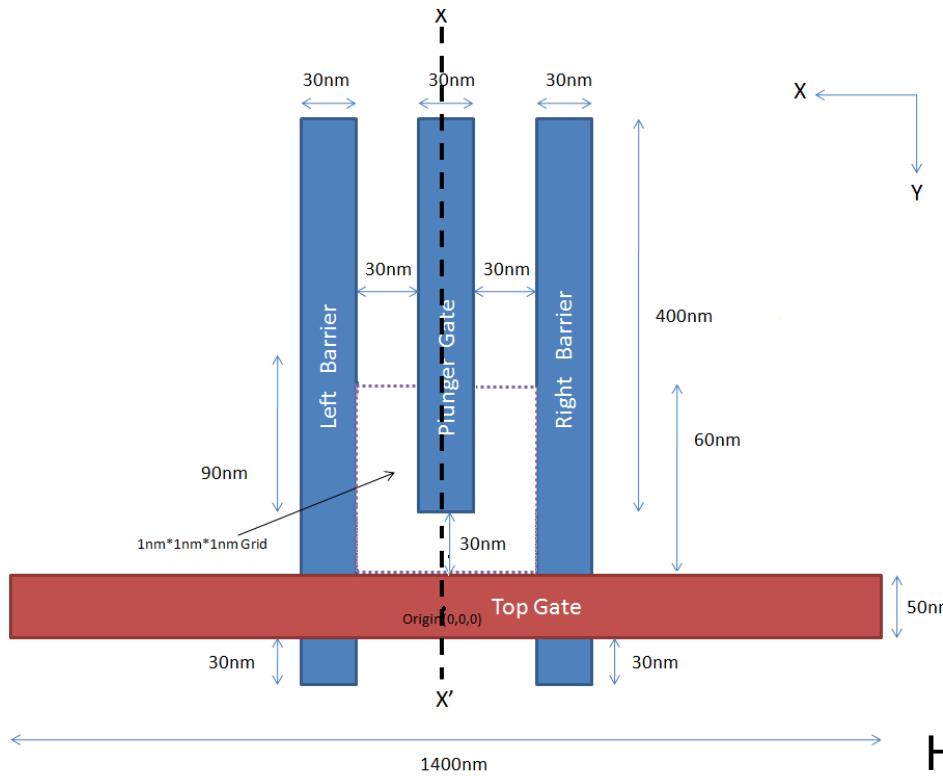
Atomistic tight-binding (NEMO 3D)

- LCAO, full bandstructure method (no extra parameter for VS)
- miscut (tilt)
- surface roughness
- alloy disorder
- strain
- hetero-structures
- realistic device geometries
- E-fields
- B-fields
- multi-million atom systems (HPC)

Configuration Interaction
E. Nielsen, et. al. PRB 82, 075319 (2010).

- Few electron full Hamiltonian
- J, K in k-space
- Computational speed (HPC)

1. Hyperfine Stark Effect (CQC2T)



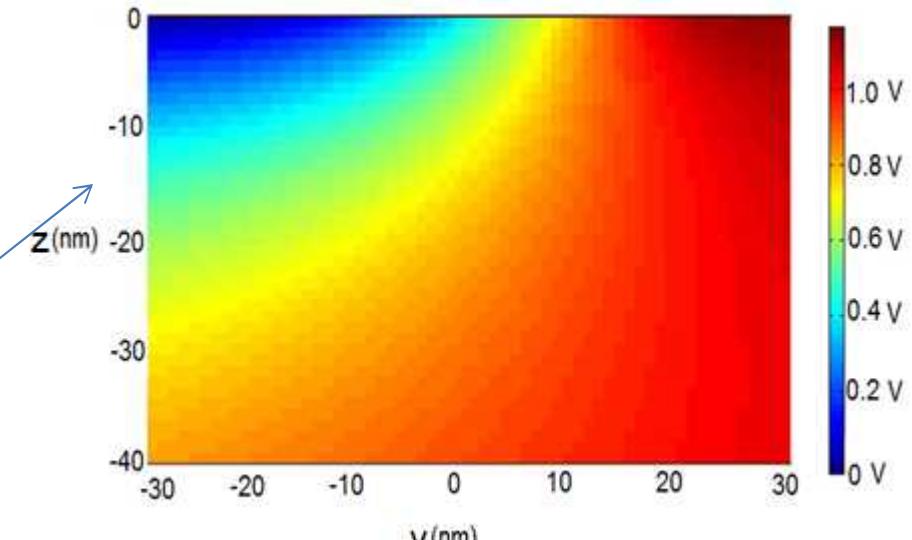
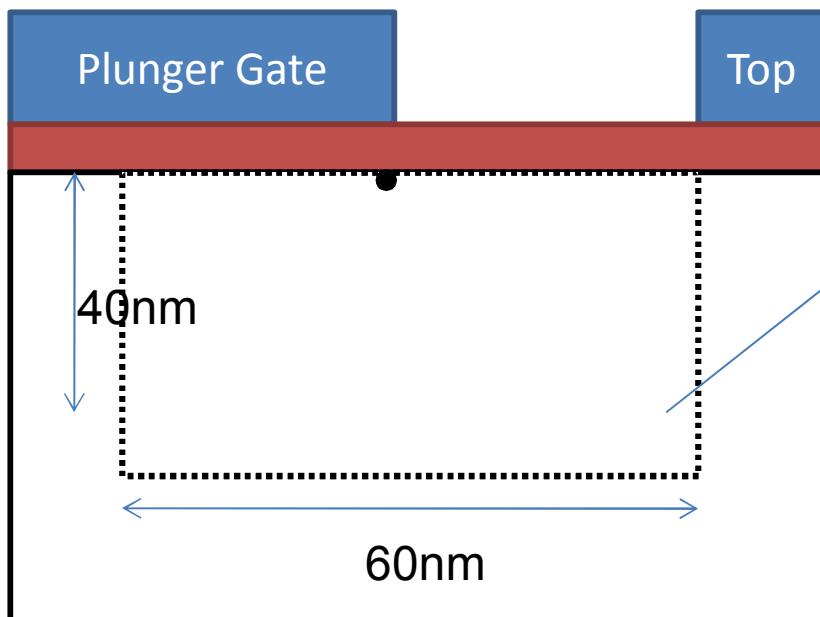
$$A(E) \longrightarrow |\Psi(E, r_0)|^2$$

Hyperfine resonance measured: 2.8 mT

Hyperfine resonance of bulk P: 4.2 mT

Collaboration: F. Mahiyaddin, A. Morello, A. Dzurak, L. Hollenberg

Hyperfine Stark Effect (CQC2T)



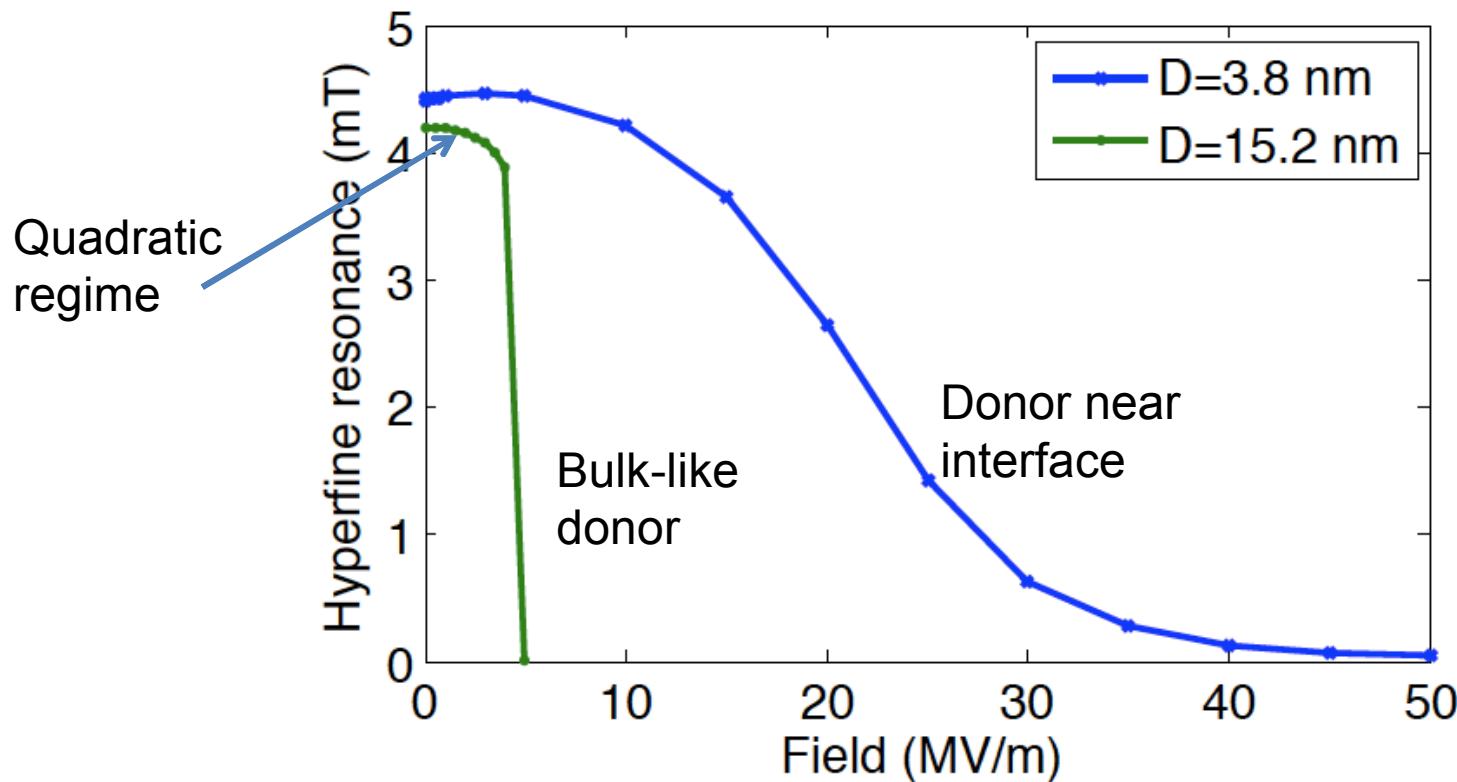
NEXT_NANO (3D potential)

Top Gate = 1.5V

Plunger Gate = -1.875V

Barriers – 0.625V

High Field Hyperfine Stark Effect

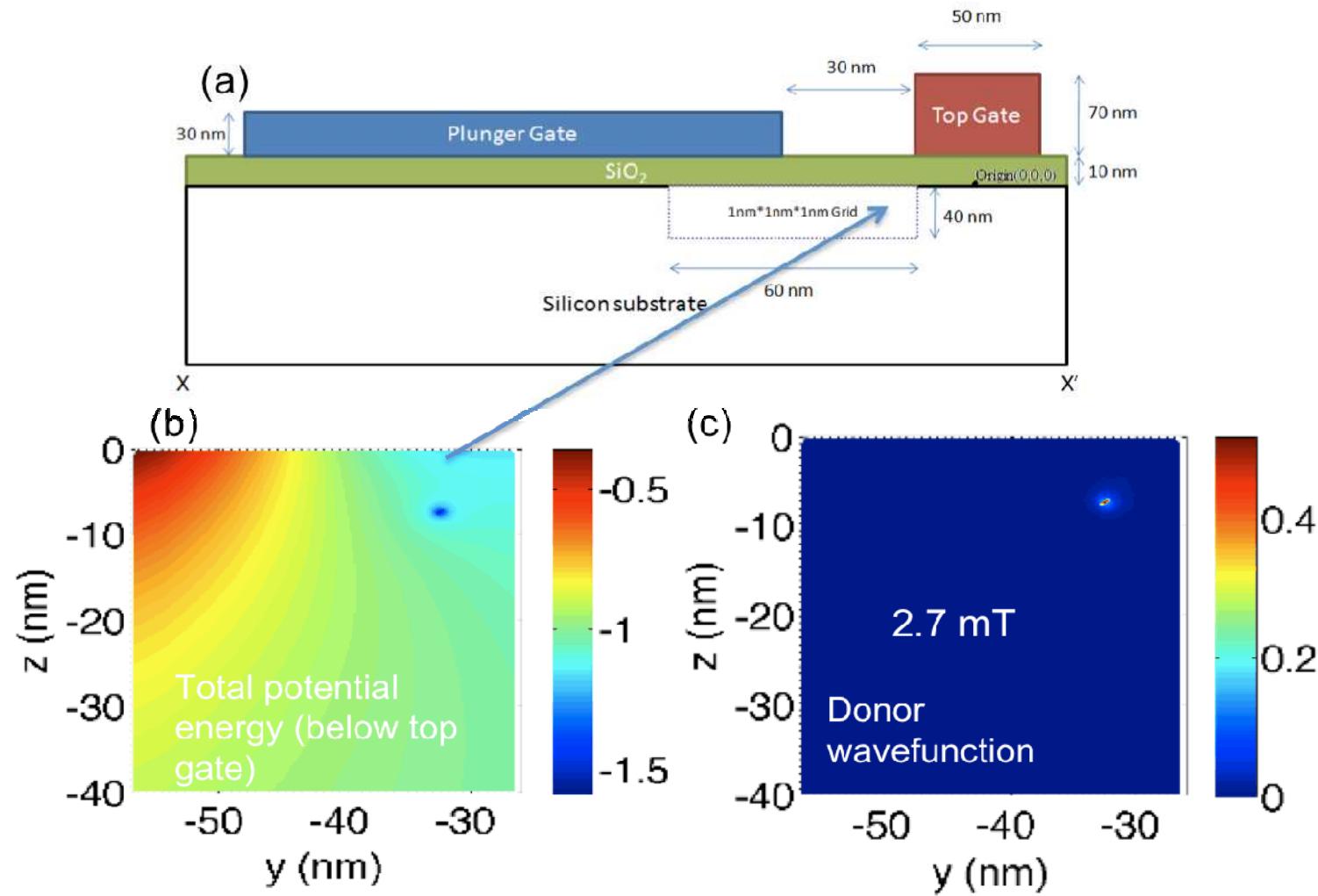


Theory: Rahman et al. PRL 99,
036403 (2007)

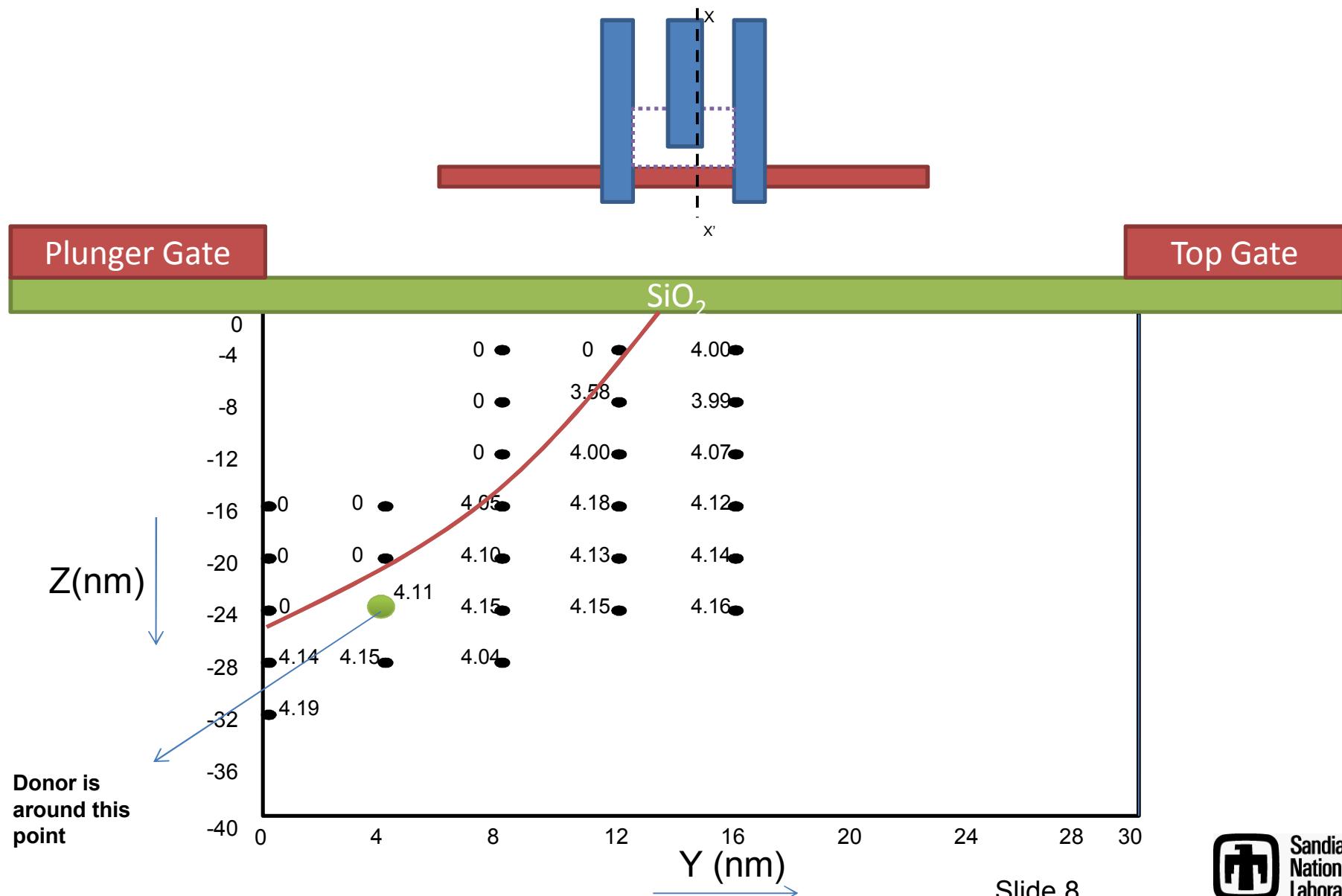
High-field regime accessible
due to surface hybridization

Bulk donors – ionization limited

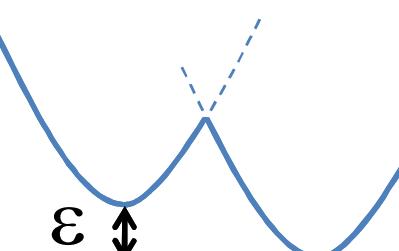
CQC2T measurements explained



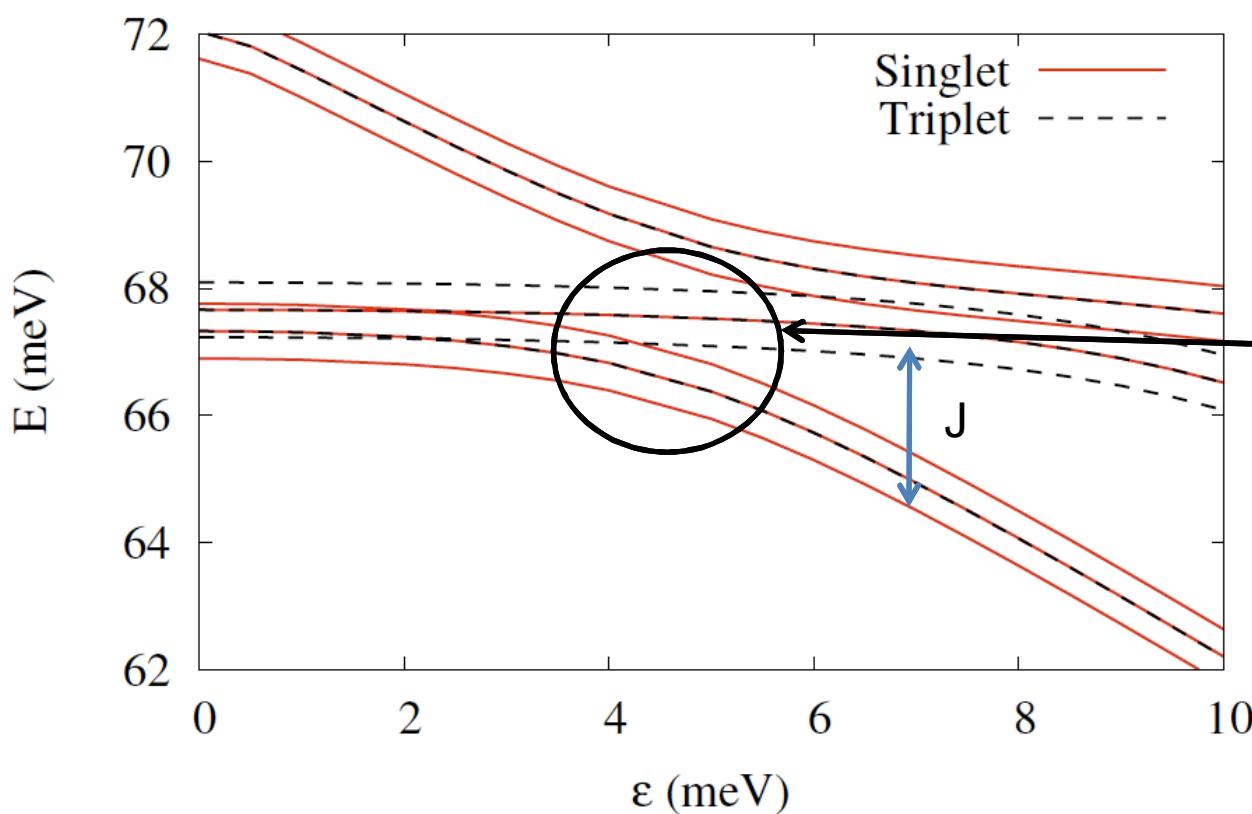
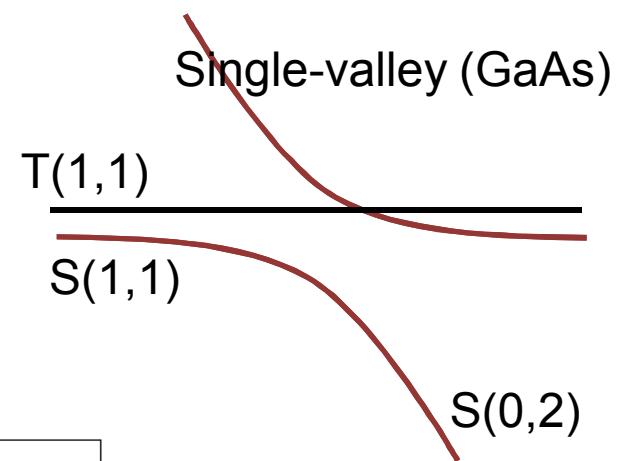
Device 1 – Contact Hyperfine (mT) at different locations of donor Slice x at 10 nm from centre of plunger towards barriers



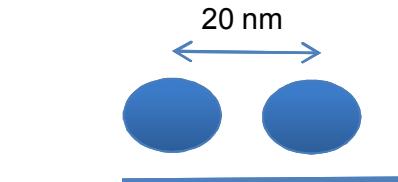
2. Ideal DQD 2e states (NEMO+CI)



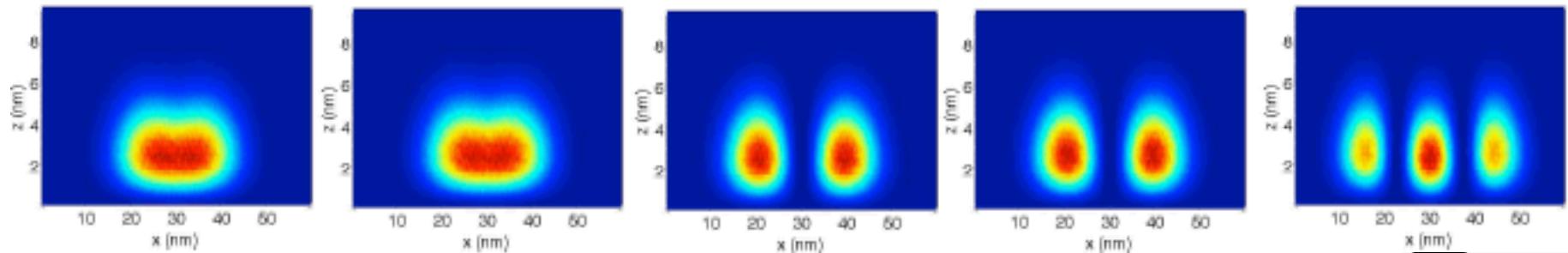
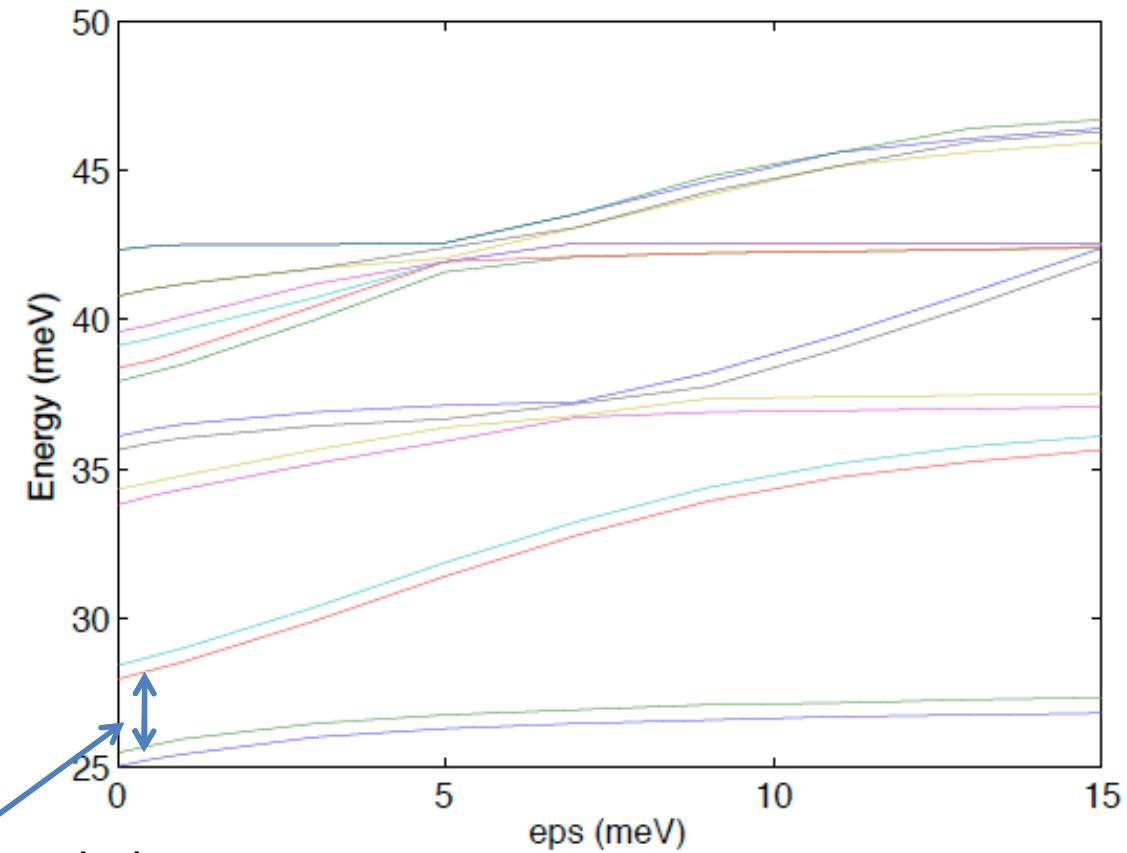
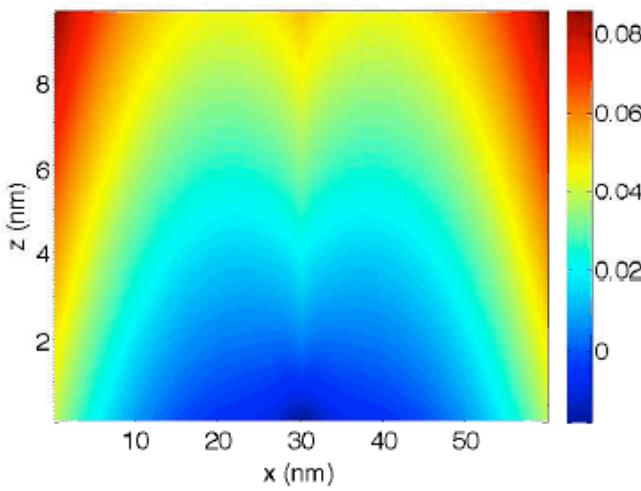
TB+CI



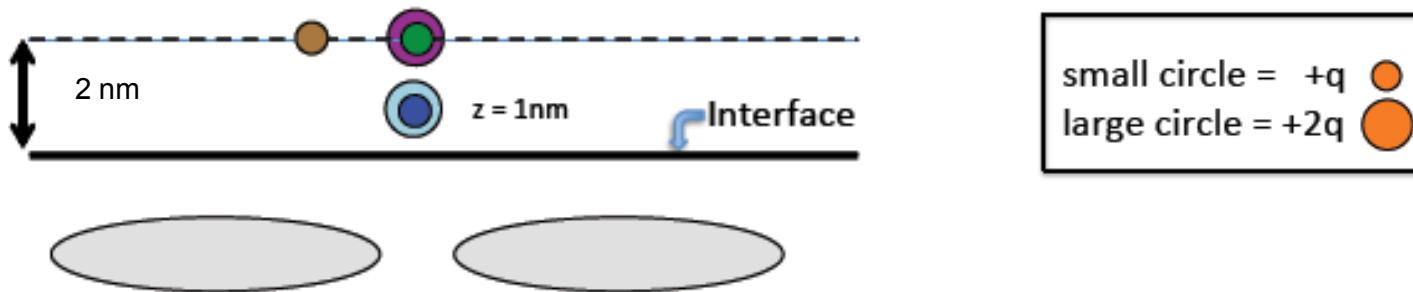
Defect at tunnel barrier (1e states)



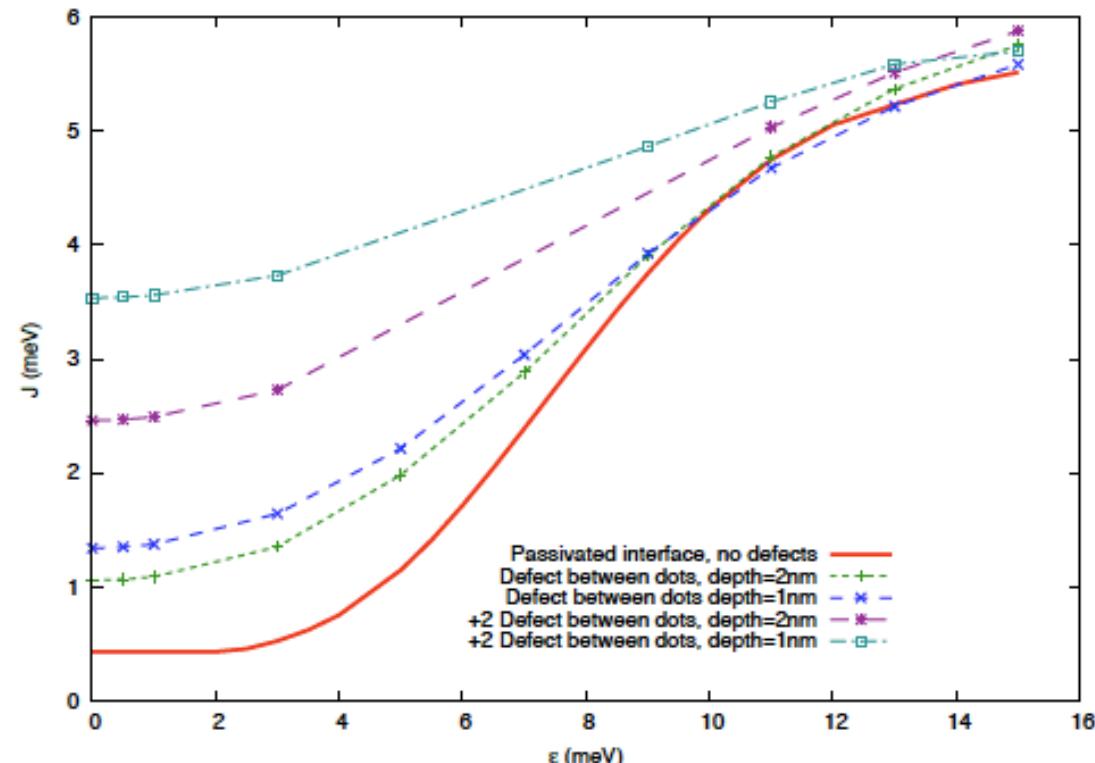
potential



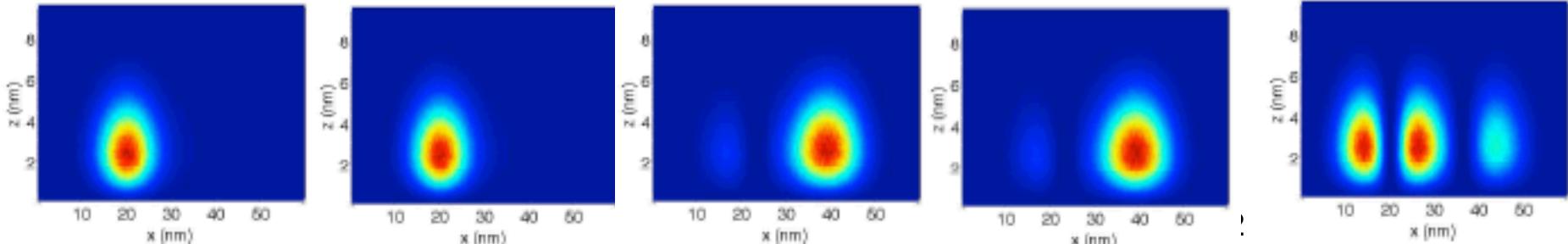
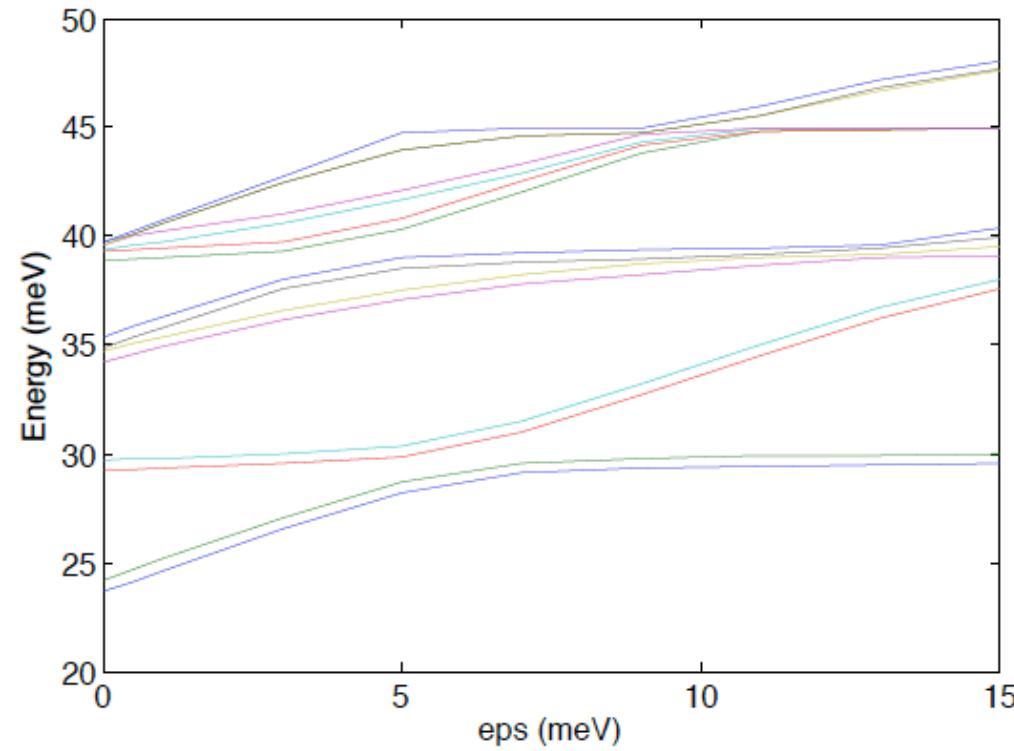
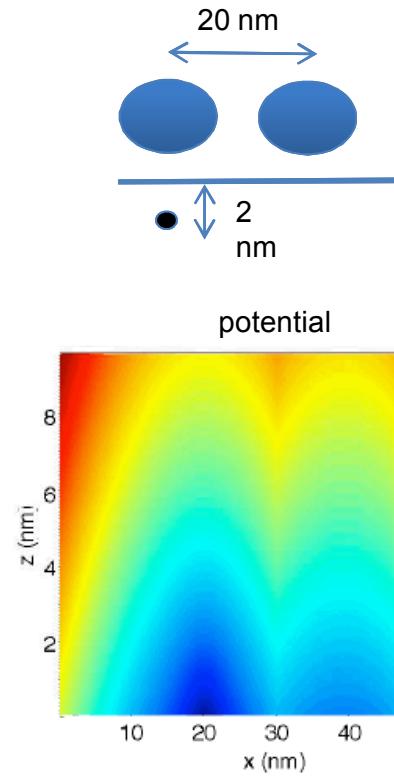
Defect at tunnel barrier between dots



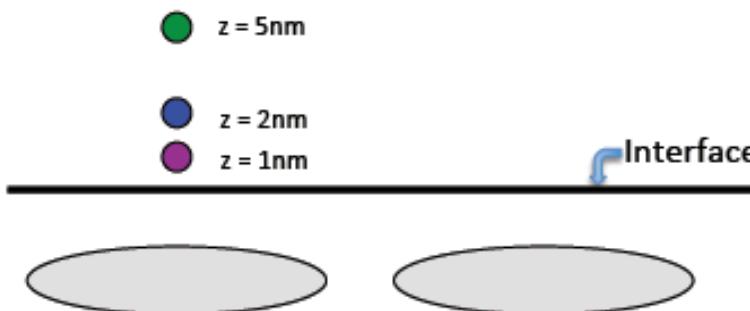
- Curve flattens as tunnel barrier is lowered
- Exchange at zero detuning increases
- J curve is sensitive to defect depth and magnitude
- Defects in the barrier can make it hard to form a DQD



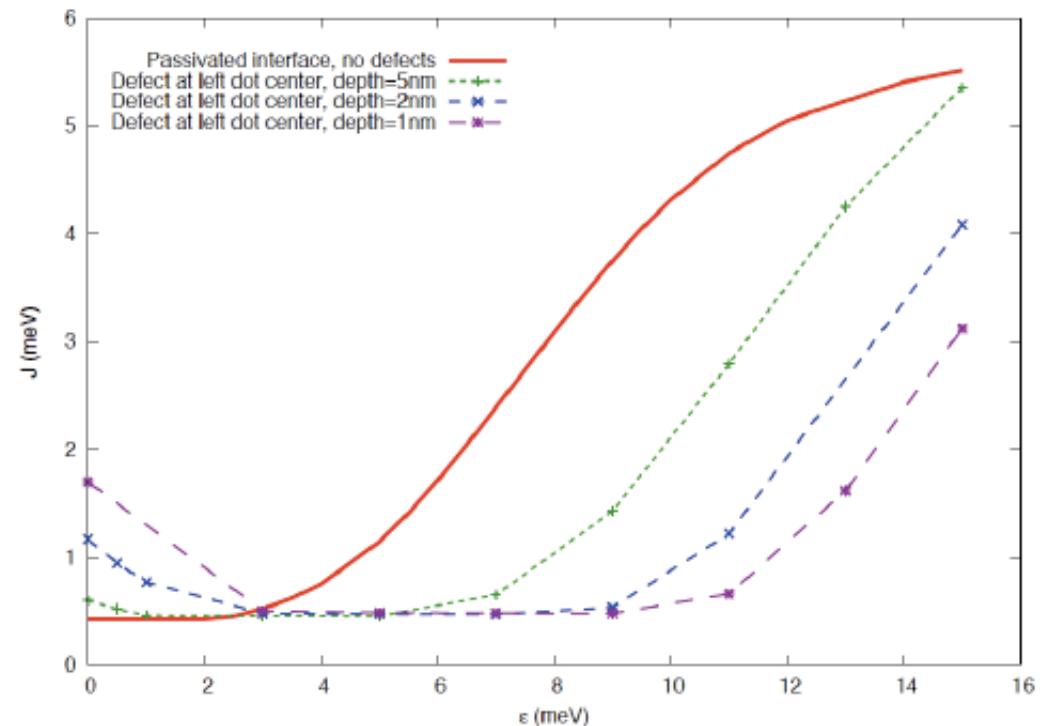
Defect at center of one dot (1e states)



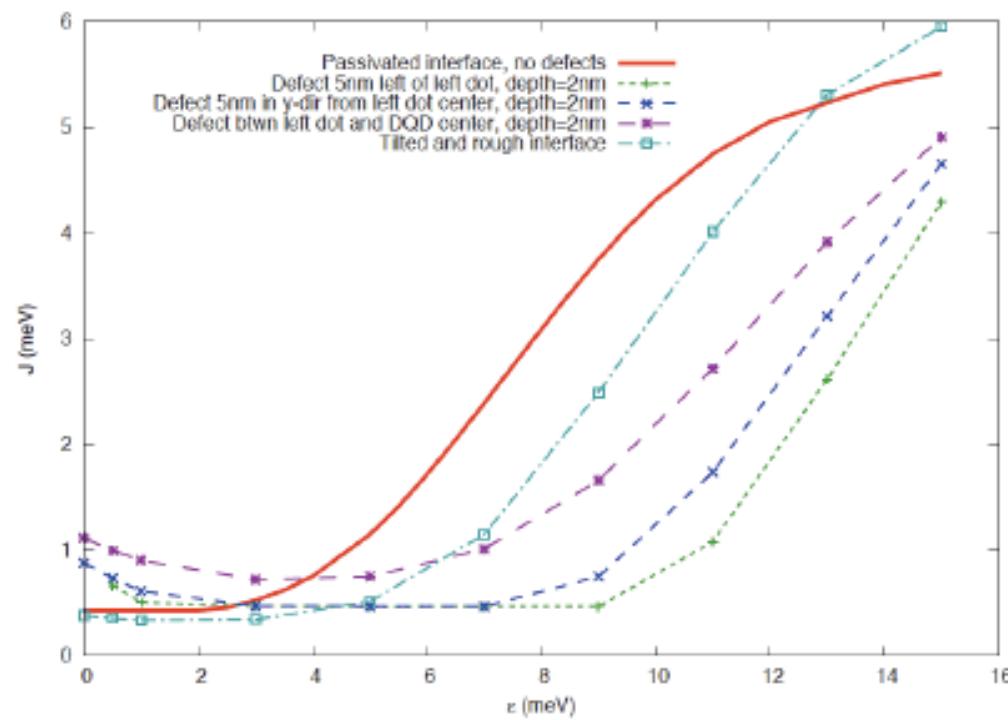
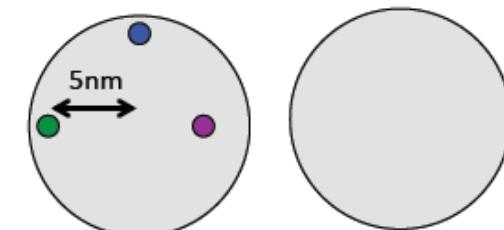
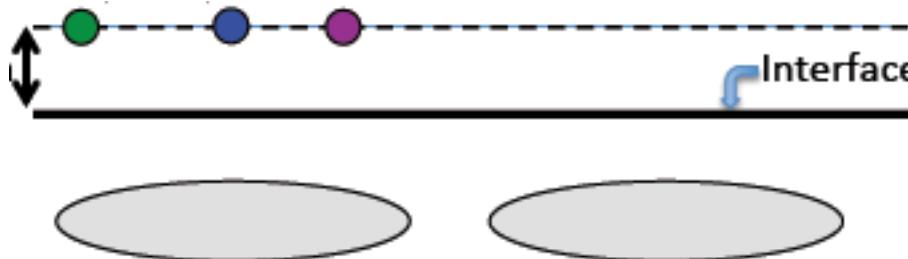
Defect at dot center



- Defect away from the tunnel barrier manifests as a shift in the J-curve (modified detuning)
- Produces asymmetry between the (0,2) and (2,0) occupation by changing the electrostatic landscape.



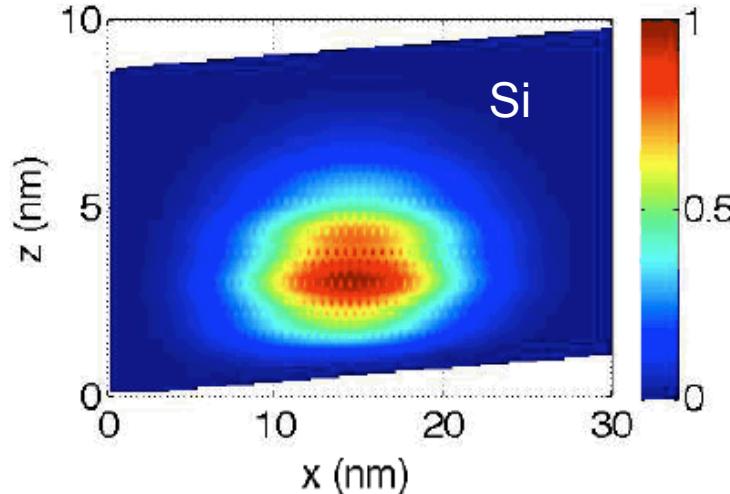
Defect at different distances from barrier



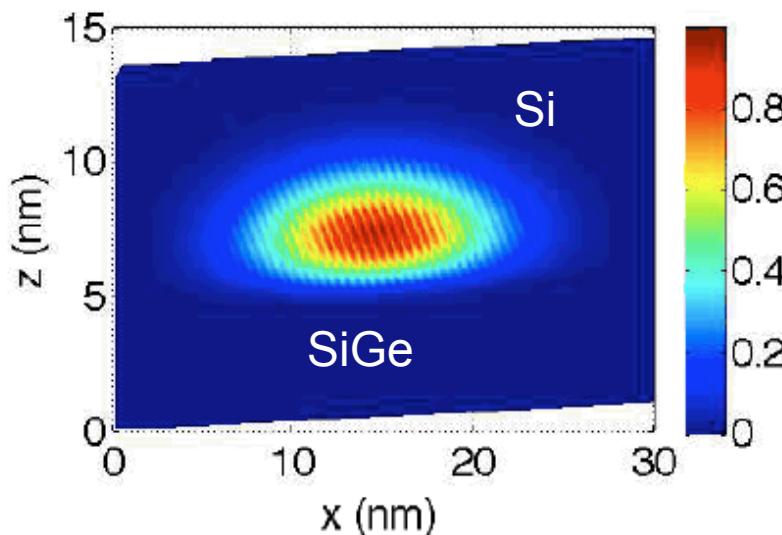
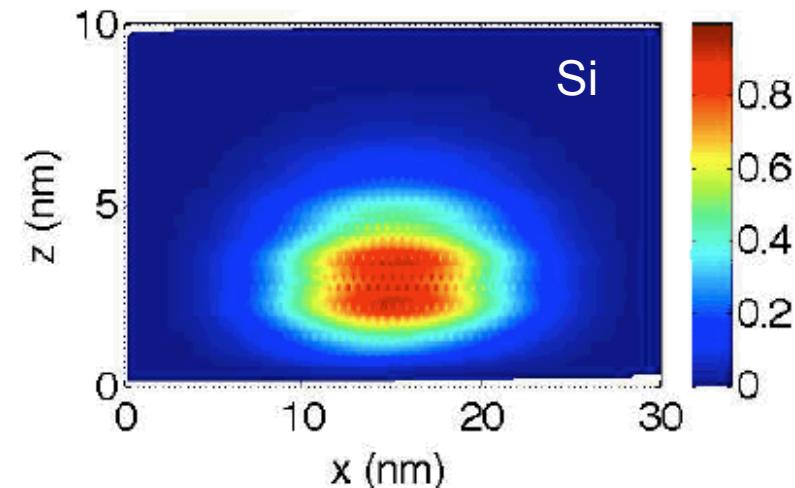
- J-curve is sensitive to defect location relative to the dots

Atomistic models of interfaces: miscuts + alloy disorder

2 degrees (step length 3.8 nm, 7:1/4)

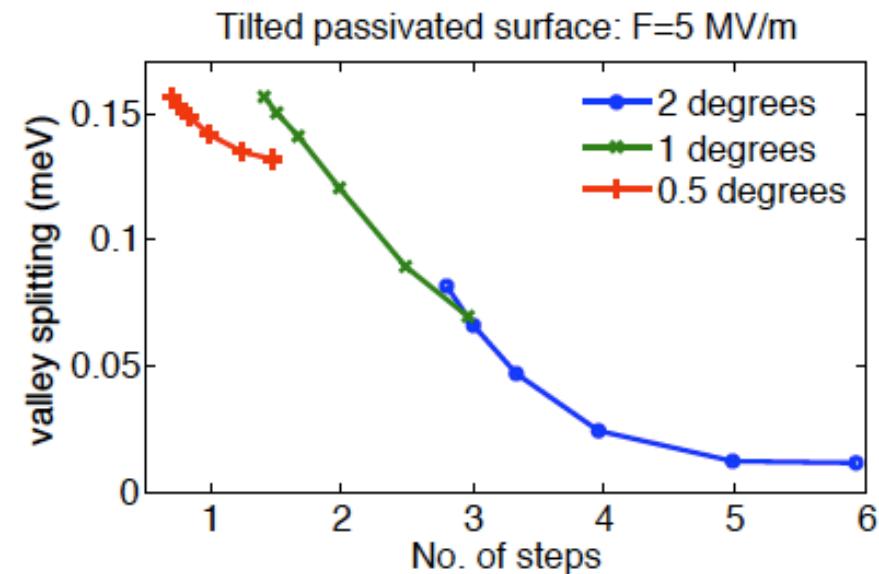
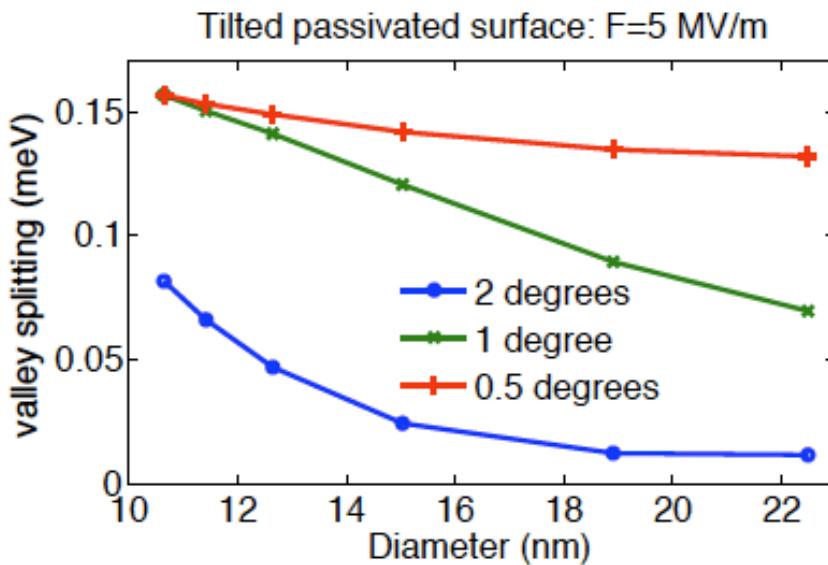


0.5 degrees (step length 15 nm, 28:1/4)



- QDs parabolic in x, y
- Uniform E-field in z (5-10 MV/m)
- 20% Ge, 80% Si
- Kharche et. al., APL 90, 092109 (2007)

Effect of tilt / ideal steps



Higher tilt suppresses VS.

At fixed tilt, larger dots \rightarrow smaller VS

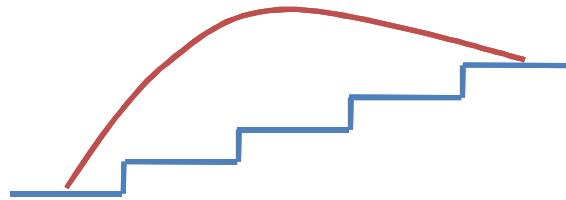
VS \rightarrow number of steps the wf samples.

E-field increases VS.

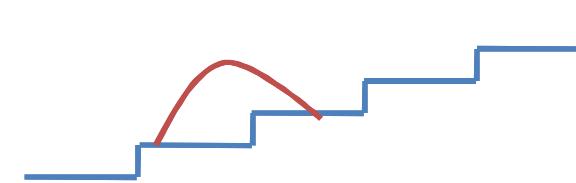
Intuition from EMT

M. Friesen et al., APL 89, 202106 (2006)

Extended wavefunction



More confined wavefunction



Step height: $a_0/4$ (monolayer)

$$\text{VS: } E_v = 2 \left| \int dr^3 e^{-i2k_0 z} |F(r)|^2 V_v(r) \right|$$

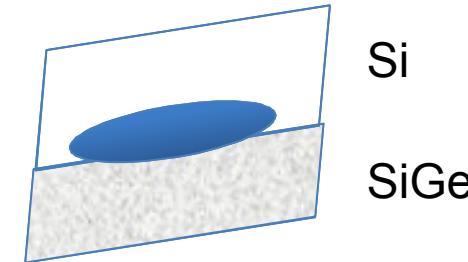
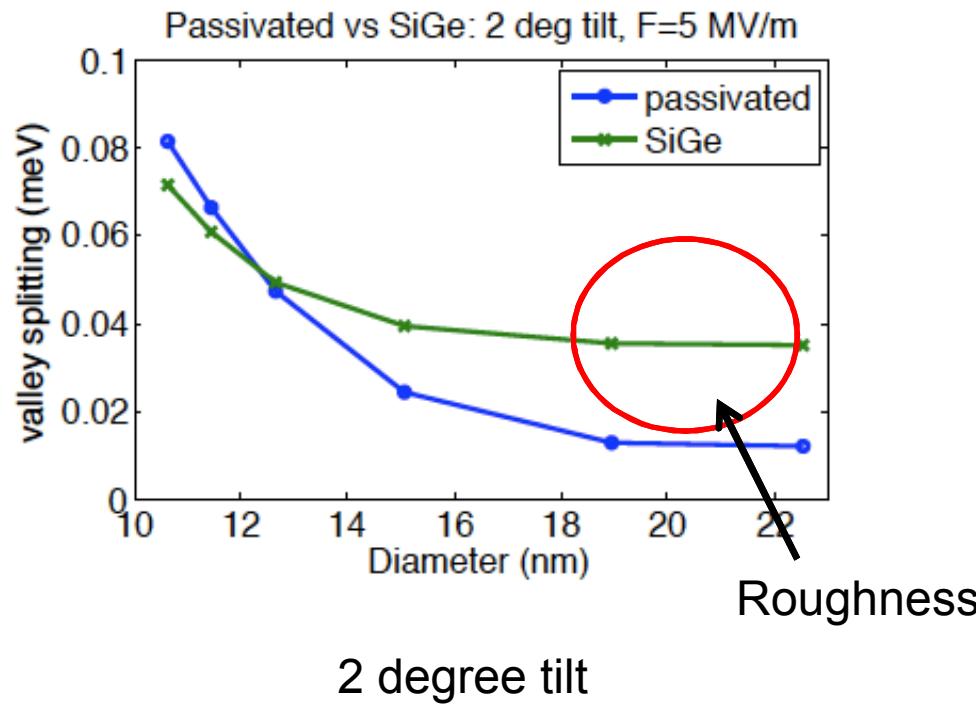
$$\text{Ideal Steps: } z = \frac{a_0}{4}$$

$$2k_0 z = 0.85\pi$$

Roughness randomizes the phase factor, cancels out the suppression.

Effect of barrier material (alloy disorder)

Passivated vs. SiGe barriers

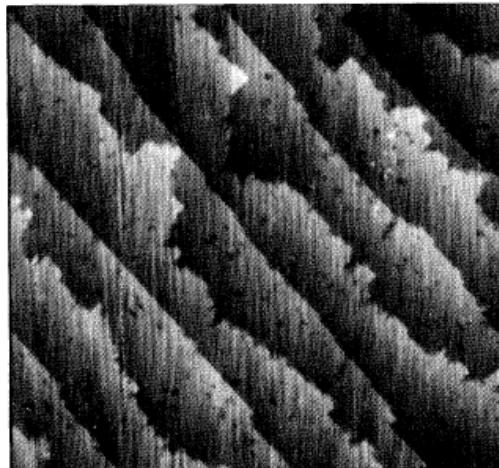


Alloy disorder \rightarrow atomistic fluctuations in CB edge.

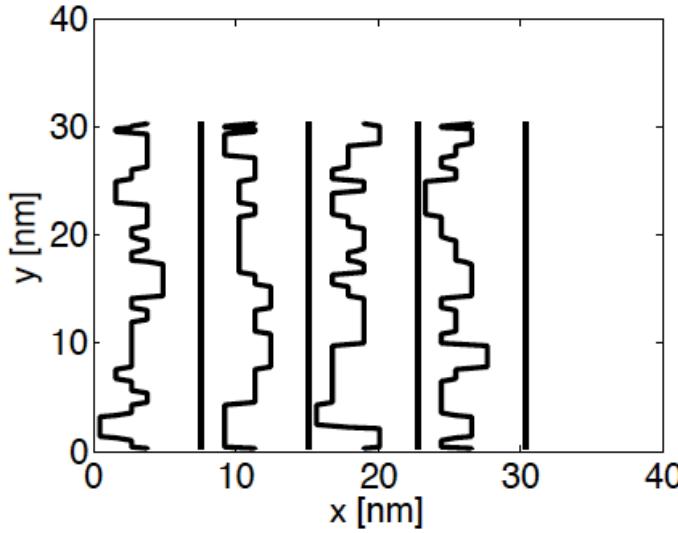
Less quantum confinement \rightarrow less VS.

Roughness \rightarrow increases VS (tends to nullify tilt).

Atomistic models of interfaces: step roughness



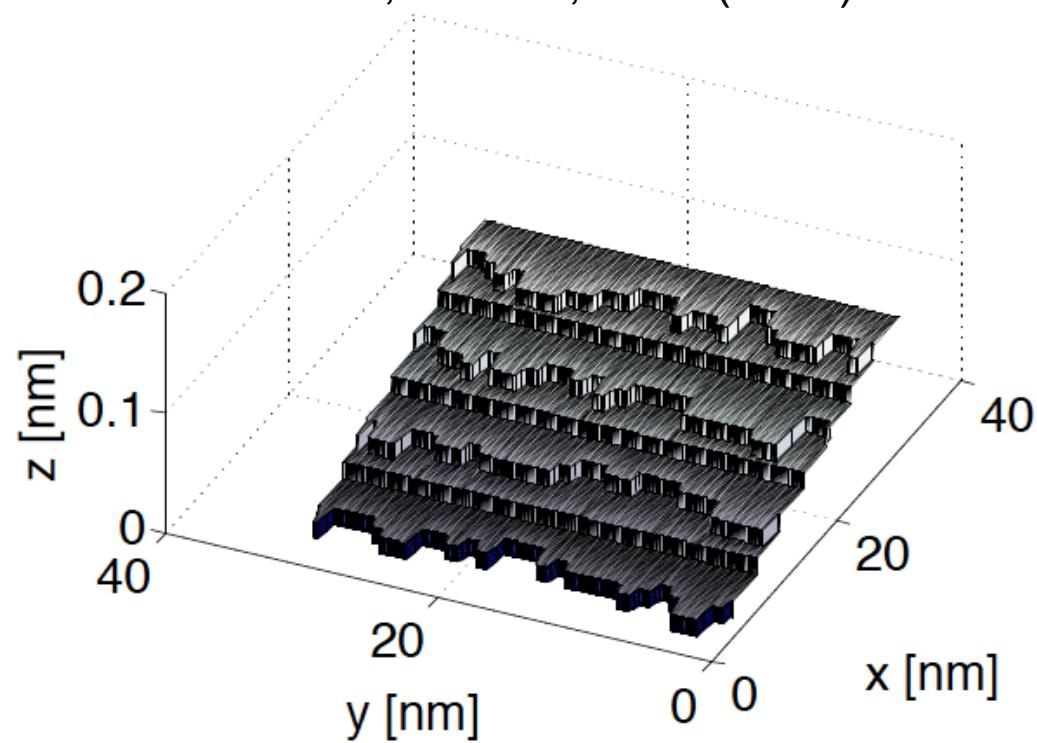
Reconstructed surfaces in y



Roughness model: alternate ideal and rough steps, Zandvliet & Elswijk, PRB 48, 14269 (1993).

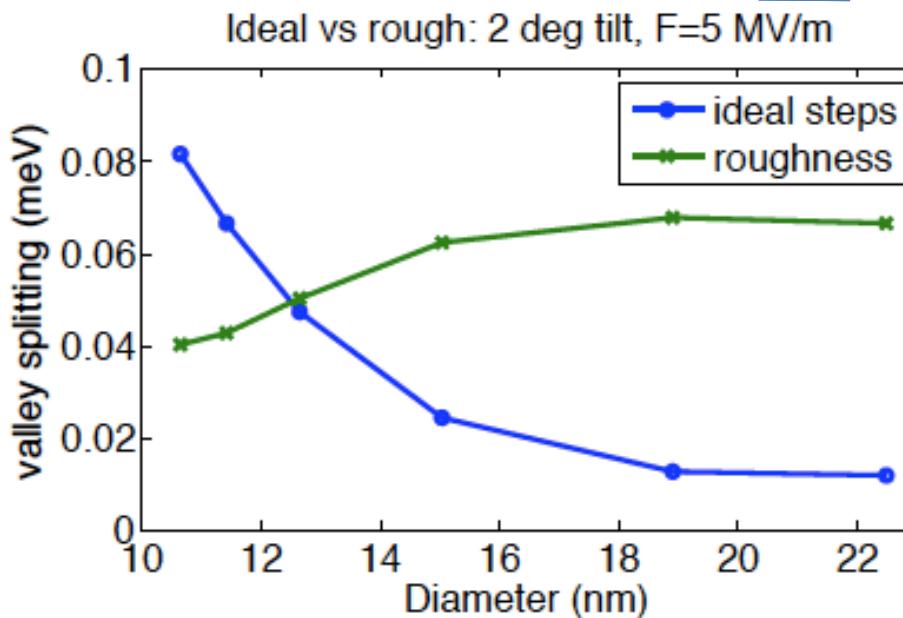
Other models:

Goodnick et al., PRB 32, 8171 (1985)
Jones et. al., PRL 75, 1570 (1995)



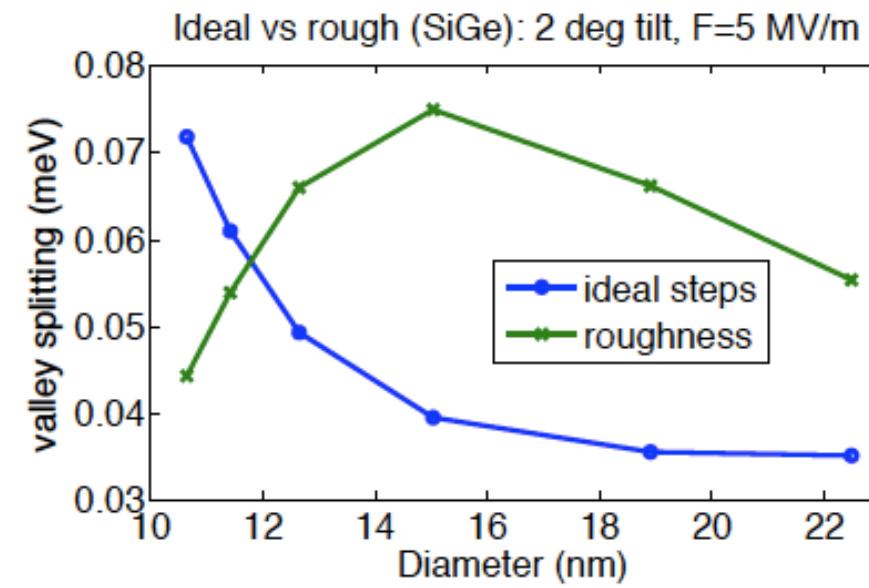
Effect of step roughness

Passivated



2 degrees

SiGe



2 degrees

Roughness increases VS: partially cancels the effect of tilt.

Alloy disordered systems are more complicated.

Future work: Different roughness profiles

Conclusions

- Atomistic tight-binding – a high precision tool for device modeling
- Hyperfine Stark effect modeling is helping to understand measurements
- Developed TB + CI methodology to investigate J-curves
- J-curves are sensitive to defect locations and densities, but mostly tunable
- Effect of valley splitting, surface roughness, miscuts can be studied